


TRANSMITTAL

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Title of Invention	Method for forming silicon dioxide film using siloxane							
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Date :	2004-02-19							
First Named Applicant:	Mr. Park Jae-Eun							
Confirmation Number:	4756							
Attorney Docket Number:	SAM-0483							
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<table border="1"><thead><tr><th>Submitted By:</th><th>Elec. Sign.</th><th>Sign. Capacity</th></tr></thead><tbody><tr><td>Mr. Anthony P. Onello Jr. Registered Number: 38,572</td><td>/Anthony P. Onello Jr./</td><td>Attorney</td></tr></tbody></table>			Submitted By:	Elec. Sign.	Sign. Capacity	Mr. Anthony P. Onello Jr. Registered Number: 38,572	/Anthony P. Onello Jr./	Attorney
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Documents being submitted:	Files
us-ids	SamsungFourEightyThreePartTwo-usidst.xml us-ids.dtd us-ids.xsl
Comments	
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